

## **AMENDMENTS TO THE CLAIMS**

The following listing of claims will replace all prior versions and listings of claims in the application.

### **LISTING OF CLAIMS**

1. (Cancelled)

2. (Currently Amended) An electro-optic device comprising:

an electro-optic material disposed between a pair of substrates; ~~and means for applying an electric field to the electro-optic material;~~

wherein the electro-optic material is sealed in a material-sealed region in which a reflecting electrode is formed on one of the substrates, the reflecting electrode having a laminated structure including:

an underlying conductive layer formed of a conductive metal oxide laminated on one of the substrates;

a reflective conductive layer formed on one of silver and a silver alloy laminated on the underlying conductive layer; and

a transparent conductive layer laminated on the reflective conductive layer and the underlying conductive layer; and

external wiring provided outside the material-sealed region to conductively connect to the reflecting electrode, the external wiring comprising ~~the same material layer as at least one of the underlying conductive layer and the underlying conductive layer~~ formed directly on and the transparent conductive layer ~~of the laminated structure;~~

wherein the transparent conductive layer is thinner than the underlying conductive layer.

3. (Cancelled)

4. (Cancelled).

5. (Currently Amended) A method for manufacturing an electro-optic device including an electro-optic material disposed between a pair of substrates, ~~and means for applying an electric field to the electro-optic material,~~ the method comprising:

a step of forming an underlying conductive layer formed of a conductive metal oxide on one of the substrates;

a step of selectively forming a reflective conductive layer formed of one of silver and a silver alloy on the underlying conductive layer in a first region corresponding to a material-sealed region in which the electro-optic material is sealed;

a step of forming a transparent conductive layer on the reflective conductive layer and the underlying conductive layer in the first region and directly on the underlying conductive layer in a second region out of the material-sealed region, the transparent conductive layer being thinner than the underlying conductive layer; and

a step of simultaneously patterning the underlying conductive layer and the transparent conductive layer.

6. (Cancelled)

7. (Currently Amended) ~~An electronic apparatus comprising the~~ The method for manufacturing an electro-optic device of claim ~~[[1]]~~ 5, further comprising and control means for controlling the electro-optic device with a control means.

8. (Original) The electro-optic device of claim 2, wherein the transparent conductive layer has a thickness of 5 nm to 30 nm.

9. (Original) The method for manufacturing an electro-optic device of claim 5, wherein the transparent conductive layer has a thickness of 5 nm to 30 nm.

10. (Original) An electronic apparatus comprising the electro-optic device of claim 2, and control means for controlling the electro-optic device.